

Appl. No. 10/765,531

Communication dated 07/05/2007

Attorney Docket No.: N1085-00225 (TSMC2003-0656)
N1280-00235**Amendments to the Claims:**

This listing of pending claims is as follows:

- 1 1. (Withdrawn - Currently Amended) A method for processing one or more oblique
2 features on a mask or reticle substrate, the method comprising:
3 aligning the mask or reticle substrate with a predetermined reference system;
4 determining an offset angle of a feature to be processed on the mask or reticle
5 substrate with regard to either a first reference direction or a second reference direction
6 perpendicular to the first reference direction of the predetermined reference system;
7 rotating the mask or reticle substrate in a predetermined direction by the offset
8 angle; and
9 processing the feature on the mask or reticle substrate according to the
10 predetermined reference system wherein the feature is processed in either the
11 horizontal or vertical reference direction thereof of the predetermined reference system
12 and at the offset angle with respect to an edge of the mask or reticle substrate,
13 wherein the processing the feature comprises writing a mask pattern.